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PN - JP2002164257 A 20020607

PD - 2002-06-07

PR - JP20000356995 20001124.

OPD - 2000-11-24

TI - LAMINATED CERAMIC ELECTRONIC COMPONENT

IN - AIBA TAKASHI; KUME HISASHI, OKABE MASAYUKI; YOSHII AKITOSHI

PA - TDK CORP

IC - H01G4/30 : H01G4/12

O WPI / DERWENT

 Laminated ceramic electronic component e.g. capacitor has nickel plated layer of specific thickness formed by electrodeposition plating in external terminal electrode

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PA - (DENK) TDK CORP

IC - H01G4/12;H01G4/30

AB - JP2002164257 NOVELTY - The thickness of nickel plated layer 6b ) of the external terminal electrode 6), formed by electrodeposition plating is set to 0.1-1.0 mu m.

- USE Laminated ceramic electronic components such as ceramic capacitor, varistor, dielectric resonator and piezoelectric element for electronic device.
- ADVANTAGE Excels in reliability, bending strength and heat resistance property.
- DESCRIPTION OF DRAWING(S) The figure shows an expanded sectional view of the laminated ceramic electronic component. (Drawing includes non-English language text).
- External terminal electrode 5
- Nickel plated layer 5b
- (Dwg.1/3)

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none

'AB

IN - KUME HISASHAIBA TAKASHIOKABE MASAYUKI, YOSHII AKITOSHI

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TI - LAMINATED CERAMIC ELECTRONIC COMPONENT

 PROBLEM TO BE SOLVED: To provide a satisfactorily reliable laminated ceramic electronic component having superior flexture strength and heatcycle resistance.

- SOLUTION: The laminated ceramic electronic component is formed with its external terminal electrode laminated by a first electrode layer 5a of a base electrode layer of Ag-Pd or Cu, a second electrode layer 5b of electrolytic plated layer on the first electrode layer 5a, and a third electrode layer 5c of Sn or Sn-Pb plated layer on both ends of a laminated ceramic element4, including an internal electrode 3 therein in this order and the electrolytic Ni plated layer, is formed with its thickness in a range of 0.1 to 1.0 &mu m.
- H01G4/30;H01G4/12

none

none

none